FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY, DOCKET NO. MICRON.098DV2	APPLICATION NO. Unknown	
INFORMATION DISCLOSURE STATEMENT			
BY APPLICANT	APPLICANT Basceri et al.		
(USE SEVERAL SHEETS IF NECESSARY)	FILING DATE Herewith	GROUP Unknown	

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
NH	1	5,335,138	8/2/94	Sandhu et al.	_		
1	2	5,406,445	4/11/95	Fujii et al.	-	-	
	3	5,506,166	4/9/96	Sandhu et al.		_	
	4	5,717,234	2/10/98	Si et al.		_	
	5	5,781,404	7/14/98	Summerfelt et al.			
	6	5,783,253	7/21/98	Roh		_	
	7	5,889,299	3/30/99	Abe et al.	-	_	
	8	5,973,911	10/26/99	Nishioka	_	_	
	9	6,010,931	1/4/00	Sun et al.	_		
	10	6,117,482	9/12/00	Kawahara et al.	_		
V	11	6,136,639	10/24/00	Seon	-		
WIT	12	6,319,764 B1	11/20/01	Basceri et al.	_		

EXAMINER INITIAL		OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)				
UX	13 Hiromi Itoh et al., "Integration of BST Thin Film for Dram Fabrication," (DO DATE FOR THIS DOC)					
		C. Basceri, "An Important Failure Mechanism in MOCVD (Ba Sr) TiO Thin Films: Resistance Degradation," Ferroelectric Thin Films IV, Materials Research Society, 1998, pp. 9-14 No MoNTY				
NH	15 Chung Ming Chu and Pan Lin, "Electrical Properties and Crystal Structure of a (Ba Sr) TiO3 Films Prepared at Low Temperatures on a LaNiO3 Electrode by Radio-Frequency Magnetron Sputtering, Appl. Phys. Lett., Vol. 70 (2), 13 January 1997, pp. 249-51					
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